

Amendments to the Specification:

Please replace the paragraph beginning on page 4, line 20, with the following rewritten paragraph:

In order to achieve the object as described above, the present invention adopts the following constructions corresponding to Figs. 1 to 16 as illustrated in embodiments.

~~However, parenthesized reference numerals affixed to respective elements merely exemplify the elements, with which it is not intended to limit the respective elements.~~

Please replace the paragraph beginning on page 5, line 1, with the following rewritten paragraph:

According to a first aspect of the present invention, there is provided an exposure apparatus (EX) which exposes a substrate (P) by radiating an exposure light beam (EL) onto the substrate (P) through a liquid (LQ); the exposure apparatus comprising a substrate stage (PST) which has a substrate-holding member (PH) for holding the substrate (P) and which is movable while holding the substrate (P) by the aid of the substrate-holding member (PH); and a temperature adjustment system (60) which performs temperature adjustment for the substrate-holding member (PH).

Please replace the paragraph beginning on page 6, line 3, with the following rewritten paragraph:

According to a second aspect of the present invention, there is provided an exposure apparatus (EX) which exposes a substrate (P) by radiating an exposure light beam (EL) onto

the substrate (P) through a liquid-(LQ); the exposure apparatus comprising a temperature adjustment system (60) which performs temperature adjustment for an optical member (for example, 2, 401, 501) through which the exposure light beam (EL) passes in a state in which the optical member makes contact with the liquid-(LQ).

Please replace the paragraph beginning on page 7, line 23, with the following rewritten paragraph:

According to a third aspect of the present invention, there is provided an exposure apparatus (EX) which exposes a substrate (P) by radiating an exposure light beam (EL) onto the substrate (P) through a liquid-(LQ); the exposure apparatus comprising a substrate stage (PST) which is movable while holding the substrate (P) and which has a member (50, 300, 401, 501 or the like) forming a flat portion (51, 301A, 401A, 501A or the like) around the substrate (P); and a temperature adjustment system (60) which performs temperature adjustment for the member (50, 300, 401, 501 or the like) forming the flat portion (51, 301A, 401A, 501A or the like).

Please replace the paragraph beginning on page 9, line 1, with the following rewritten paragraph:

According to a fourth aspect of the present invention, there is provided an exposure apparatus (EX) which exposes a substrate (P) by radiating an exposure light beam (EL) onto the substrate (P) through a liquid-(LQ); the exposure apparatus comprising a first substrate stage (PST1) which has a substrate-holding member (PH1) for holding the substrate (P) and which is movable while holding the substrate (P) by the aid of the substrate-holding member

(PH1); a second substrate stage (PST2) which has a substrate-holding member (PH2) for holding the substrate (P) and which is movable while holding the substrate (P) by the aid of the substrate-holding member (PH2); a measuring station (ST1) which performs measurement for the substrate (P) held by one of the stages (PST1 or PST2); an exposure station (ST2) which performs exposure for the substrate (P) held by the other of the stages (PST2 or PST1); and temperature adjustment systems (60) which are provided for the first substrate stage (PST1) and the second substrate stage (PST2) respectively and which perform temperature adjustment for the substrate-holding member (PH1, PH2) of each of the stages in the measuring station (ST1).

Please replace the paragraph beginning on page 10, line 13, with the following rewritten paragraph:

According to a fifth aspect of the present invention, there is provided an exposure apparatus (EX) which exposes a substrate (P) by radiating an exposure light beam onto the substrate (P) through a liquid (LQ); the exposure apparatus comprising a liquid supply mechanism (10) which supplies the liquid (LQ); and a temperature sensor (80, 82, 83, 84) which measures a temperature of an object (P, 2, 50, 300, 401, 501 or the like) that makes contact with the liquid (LQ) supplied from the liquid supply mechanism (10); wherein the liquid supply mechanism (10) adjusts a temperature of the liquid to be supplied on the basis of a measurement result obtained by the temperature sensor (80, 82, 83, 84).

Please replace the paragraph beginning on page 11, line 21, with the following rewritten paragraph:

According to the present invention, there is provided a method for producing a device, comprising using the exposure apparatus (EX) according to any one of the aspects described above. According to the present invention, the device, which exhibits the desired performance, can be produced by using the exposure apparatus which is capable of satisfactorily performing the exposure process and the measurement process through the liquid.

Please replace the paragraph beginning on page 12, line 3, with the following rewritten paragraph:

According to a sixth aspect of the present invention, there is provided an exposure method for exposing a substrate (P) by radiating an exposure light beam (EL) onto the substrate (P) through a liquid (LQ); the exposure method comprising adjusting a temperature of the substrate (P) in consideration of a temperature of the liquid (LQ) before starting exposure for the substrate (P); and exposing the substrate (P) by radiating the exposure light beam (EL) onto the substrate (P) through the liquid (LQ).

Please replace the paragraph beginning on page 13, line 9, with the following rewritten paragraph:

According to a seventh aspect of the present invention, there is provided an exposure method for exposing a substrate (P) through a liquid (LQ); the exposure method comprising

adjusting a temperature of an object (P, 2, 50, 300, 401, 501 or the like) which includes the substrate and makes contact with the liquid, on the basis of a predetermined temperature; and exposing the substrate through the liquid which has the predetermined temperature. In this exposure method, the temperature of the object is adjusted on the basis of the temperature (predetermined temperature) of the liquid brought about when the liquid immersion exposure is performed. Therefore, it is possible to avoid the variation of the factor which affects the image formation characteristic, including, for example, the refractive index and the temperature of the liquid, while the variation would be otherwise caused by the contact of the liquid with the object. Therefore, it is possible to guarantee the exposure accuracy of the liquid immersion exposure and the measurement accuracy before the liquid immersion exposure.

Please replace the paragraph beginning on page 14, line 3, with the following rewritten paragraph:

According to an eighth aspect of the present invention, there is provided an exposure method for exposing a substrate by radiating an exposure light beam (EL) onto the substrate (P) through a liquid (LQ); the exposure method comprising supplying the liquid (LQ); and adjusting a temperature of the liquid (LQ) to be supplied, on the basis of a temperature of an object (P, 2, 50, 300, 401, 501 or the like) which makes contact with the supplied liquid (LQ). According to this exposure method, the temperature of the supplied liquid is adjusted on the basis of the temperature of the object such as the substrate which makes contact with the liquid. Therefore, it is possible to suppress the temperature change of the object, thereby maintaining the temperature of the liquid supplied onto the object to be in the desired state.